	Hits	Search Text	DBs
1		isame cremovs4 or eliminars4 or	US-PGPUB; USPAT; EPO; JPO; DERWENT; IBM_TDB
2	1	((object or substrate or wafer) same (resin or photoresist or resist) same cur\$4) and ((stor\$4 near9 (device or container or holder)) same (liquid or solvent or ether or	

	Hits	Search Text	DBs
3	5		
4	19	((object or substrate or wafer) same (resin or photoresist or resist) same cur\$4) and ((stor\$4 near9 (device or container or holder)) same (liquid or solvent or ether or (TPM near6 ether)) same (remov\$4 or eliminat\$4 or	US-PGPUB; USPAT; EPO; JPO; DERWENT; IBM_TDB

	Hits	Search Text	DBs
5	12	ether)) same (remov\$4 or eliminat\$4 or dissolv\$4 or	US-PGPUB; USPAT; EPO; JPO; DERWENT; IBM_TDB

	Hits	Search Text	DBs
6	44	(resin\$4 or photoresist or resist or polymer\$3) same	US-PGPUB; USPAT; EPO; JPO; DERWENT; IBM_TDB

	Hits	Search Text	DBs
7	15	ether)) same (remov\$4 or dissolv\$4 or develop\$4) same	US-PGPUB; USPAT; EPO; JPO; DERWENT; IBM_TDB

	Hits	Search Text	DBs
8	0	photoresist or resist or polymer\$3) same (immers\$4 or	US-PGPUB; USPAT; EPO; JPO; DERWENT; IBM_TDB

	Hits	Search Text	DBs
9	0	solubilizș5) same (resinș4 or photoresist or resist or	

	Hits	Search Text	DBs
10	10	(resin\$4 or photoresist or resist or polymer\$3) same	US-PGPUB; USPAT; EPO; JPO; DERWENT; IBM_TDB

	Hits	Search Text	DBs
11	101	photoresist or resist or polymers3) same (conductivits4	US-PGPUB; USPAT; EPO; JPO; DERWENT; IBM_TDB

	Hits	Search Text	DBs
12	25	pnotoresist or resist or polymer\$3) same (conductivit\$4 or electric\$4 or conduct\$4 or	US-PGPUB; USPAT; EPO; JPO; DERWENT; IBM_TDB

]	Hits	Search Text	DBs
13 5	56	polymer\$3) same (conductivit\$4 or electric\$4 or conduct\$4 or resistance or	US-PGPUB; USPAT; EPO; JPO; DERWENT; IBM_TDB

	Hits	Search Text	DBs
14	40	resistivity or resistance or impedance) same (alter\$4 or	US-PGPUB; USPAT; EPO; JPO; DERWENT; IBM_TDB

	Hits	Search Text	DBs
15	83	chang\$4 or increas\$4 or vary\$4)	JPO; DERWENT;
16	53	((bath or (storage near9 device) or solution or liquid or solvent) same (resin\$4 or photoresist or resist or polymer\$3) same (conductivit\$4 or electric\$4 or conduct\$4 or resistivity or resistance or impedance) same (alter\$4 or chang\$4 or increas\$4 or vary\$4)	JPO; DERWENT;

	Hits	Search Text	DBs
17	40	resistivity or resistance or	US-PGPUB; USPAT; EPO; JPO; DERWENT; IBM_TDB
18	47		US-PGPUB; USPAT; EPO; JPO; DERWENT; IBM_TDB

	Hits	Search Text	DBs
19	54	increas\$4 or vary\$4) same	US-PGPUB; USPAT; EPO; JPO; DERWENT; IBM_TDB
20	15	SZI NOT SZO	US-PGPUB; USPAT
21	6	(((stor\$4 near9 device) or container or holder or bath) same (liquid or solvent or solution or ether or (TPM near6 ether) or (\$4propylene near8 glycol near12 ether)) same (remov\$4 or dissolv\$4 or develop\$4 or solubiliz\$5 or strip\$4) same (resin\$4 or photoresist or resist or polymer\$3) same (conductivit\$4	US-PGPUB; USPAT; EPO; JPO; DERWENT; IBM_TDB

	Hits	Search Text	DBs
22	3	electric\$4 or current) same (polymer\$4 or resin or resist or photoresist) same (LED or (light near5 emit\$5 near6 diode)) same (ammeter or (current near9 meter)))	US-PGPUB; USPAT; EPO; JPO; DERWENT; IBM_TDB
23	185	or impedance or resistance or electric\$4 or current) same	US-PGPUB; USPAT; EPO; JPO; DERWENT; IBM_TDB
24	266	((monitor\$4 or determin\$4 or calculat\$4 or measur\$4) same (conductivit\$4 or conductance or impedance or resistance or electric\$4 or current) same	US-PGPUB; USPAT; EPO; JPO; DERWENT; IBM_TDB

	Hits	Search Text	DBs
25	1	((monitor\$4 or determin\$4 or calculat\$4 or measur\$4) same (conductivit\$4 or conductance or impedance or resistance or electric\$4 or current) same (resin or photoresist or resist or polymer\$4) same ((light near5 emit\$5 near6 diode) or ammeter or (current near9 meter) or galvanometer or voltmeter or (conductivity near9 meter)) and (\$3propylene near12 glycol near10 methyl near12 ether)	US-PGPUB; USPAT; EPO; JPO; DERWENT; IBM_TDB
26	7	resist) same (cur\$4 or expos\$4	US-PGPUB; USPAT; EPO; JPO; DERWENT; IBM_TDB
27	10	((object or substrate or wafer or plate or template) same (resin\$4 or photoresist or resist) same (cur\$4 or expos\$4 or irradiat\$4) same laser) and	US-PGPUB; USPAT; EPO; JPO; DERWENT; IBM_TDB
28	11	resist) same (cur\$4 or expos\$4	US-PGPUB; USPAT; EPO; JPO; DERWENT; IBM_TDB

	Hits	Search Text	DBs
29		((object or substrate or wafer or plate or template) same (resin\$4 or photoresist or resist) same (cur\$4 or expos\$4 or irradiat\$4)) and (strip\$4 same (\$3propylene near12 glycol near10 methyl near12 ether))	US-PGPUB; USPAT; EPO; JPO; DERWENT; IBM_TDB
30	44	S31 NOT S30	US-PGPUB; USPAT; EPO; JPO; DERWENT; IBM_TDB
31	48	resist) same (cur\$4 or expos\$4 or irradiat\$4) same laser) and	US-PGPUB; USPAT; EPO; JPO; DERWENT; IBM_TDB
32	113		US-PGPUB; USPAT; EPO; JPO; DERWENT; IBM_TDB

	Hits	Search Text	DBs
33		_	US-PGPUB; USPAT; EPO; JPO; DERWENT; IBM_TDB
34	30	USFrins4 same (resin or	US-PGPUB; USPAT; EPO; JPO; DERWENT; IBM_TDB